Session: TH2C

Scattering Parameter and Dielectric Measurements

Chair

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Scattering parameters remain a foundation for a host of more detailed measurements. New techniques are advancing on-wafer measurements further into the millimeter-wave regime. Simultaneously, many of the new calibration techniques, particularly for on-wafer measurements, are being applied to dielectric material characterization. Many of the dielectric characterization requirements are related to microelectronic applications, including electronic packaging.

10:20 am - 12:10 pm Thursday, June 20, 1996
Room 133